

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. #25	Serial No. 09/388,989
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Cohen, et al.	Confirmation No.: 4766
(Use several sheets if necessary)		Filing Date September 2, 1999	Group 1762
Examiner M.L. Padgett			

U.S. Patent Documents

*Examiner Initial	Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1					
	A2					
	A3					
	A4					
	A5					
	A6					
	A7					
	A8					
	A9					
	A10					
	A11					
	A12					

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Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
<i>MLP</i>	B1	00/34997	06/15/2000	WO <i>Cohen et al</i>	H01L	21/311	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>MLP</i>	B2	1 077 476	02/21/2001	EP	H01L	21/311	<input checked="" type="checkbox"/>	<input type="checkbox"/>
<i>MLP</i>	B3	56155526	01/12/1981	JP <i>Yamazaki</i>	H01L	21/205	<input type="checkbox"/>	<input checked="" type="checkbox"/>

OTHER ART

*Examiner Initial	Including Author, Title, Date, Pertinent Pages, Etc.
<i>MLP</i>	C1 "Low dielectric constant films prepared by plasma-enhanced chemical vapor deposition from tetramethylsilane" by A. Grill and V. Patel, Journal of Applied Physics, Vol. 85, pages 3314-3318, March 28, 2003, March 15, 1999
<i>MLP</i>	C2 "The reduction of copper oxide thin films with hydrogen plasma generated by an atmospheric-pressure glow discharge" by Sawada, et al., J. Phys D; Appl. Phys 29 (1996) 2539-2544, printed in the UK. <i>no month</i>
<i>MLP</i>	C3 European Search Report
Examiner <i>ML Padgett</i>	Date Considered 4/25/03

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.